

ABSTRACT OF THE DISCLOSURE

Disclosed is a method of manufacturing a two-dimensional phase type element, which includes the steps of forming, on a substrate, a first etching mask in a checkered pattern, forming segments of multiple levels at a portion not covered by the first mask, forming a second etching mask corresponding to an inversion of the first etching mask, removing the first etching mask, and forming segments of multiple levels at a portion not covered by the second etching mask.

SECRET